STATEMENT OF WORK FORMAT

Porous Silicon Etcher-June 16, 2014

PR: 42005203l3

Note: Only use the sections that are applicable to your service procurement.

Background

- A Wet Etching System for Porous Silicon is needed to address process control issues for current in-house projects
- The Porous Silicon Etch system will be used by users in the Detector Development Lab for etching silicon wafers for detector related devices.
- No statutory authority or special regulations apply

Scope

- The contractor shall have delivered at least three substantially similar Double-cell HF Porous Silicon Etch systems to other customers and shall provide contact information for three references to NASA\GSFC prior to order placement.
- The contractor shall deliver a Double-cell HF Porous Silicon Etching system with one electrode mount in each cell, pneumatically actuated and vapor exhausted for bench-top use, with platinum or diamond-like carbon electrodes, window for back-side illumination, PTFE pump for electrolyte circulation, temperature control, and wafer holder for 4" wafers, Programmable Power Supply and Control Software. The contractor shall provide a complete set of operation and maintenance manuals.

Requirements

- The contractor shall contact the Technical Representative within one week after receipt of order to confirm the specifications.
- The contractor shall deliver a Double-cell HF Porous Silicon Etching system with one electrode mount in each cell, pneumatically actuated and vapor exhausted for bench-top use, with platinum or diamond-like carbon electrodes, window for back-side illumination, PTFE pump for electrolyte circulation, temperature control, and wafer holder for 4" wafers, Programmable Power Supply and Control Software. The contractor shall provide a complete set of operation and maintenance manuals.
- Delivery shall be within ten weeks after acceptance of order.

Deliverables or Delivery Schedule

- The contractor shall deliver a Double-cell HF Etching system with one electrode mount in each cell, pneumatically actuated and vapor exhausted for bench-top use
- The contractor shall deliver two platinum mesh or diamond-like carbon electrodes
- The contractor shall deliver a sapphire window with fused silica support window for wafer illumination
- The contractor shall deliver a PTFE Membrane Pump system for circulating the HF
- The contractor shall deliver a 4" or 100mm wafer holder for use with the Etching System
- The Contractor shall deliver a Porous Silicon Power Supply (36V-12A) including control software for Windows 7
- The contractor shall include any applicable packing and handling expenses.
- The contractor shall prepay and add shipping expenses
- The contractor shall deliver a complete set of operation and maintenance manuals as a soft copy. An additional hard copy on cleanroom paper is optional
- The delivery schedule is seventy calendar days (10 weeks) from the date of award.

Government-Furnished Equipment and Government-Furnished Information

- No Government-furnished equipment (GPE) and Government-furnished information (GFI) is anticipated

Place of Performance

- The Porous Silicon Etcher is to be manufactured at the contractor's site and delivered to the Government site for installation. Any specialized training and installation (if necessary) shall be performed at the Government site.

Period of Performance

- **The Porous Silicon Etcher shall be delivered within Ten weeks after acceptance of order.**